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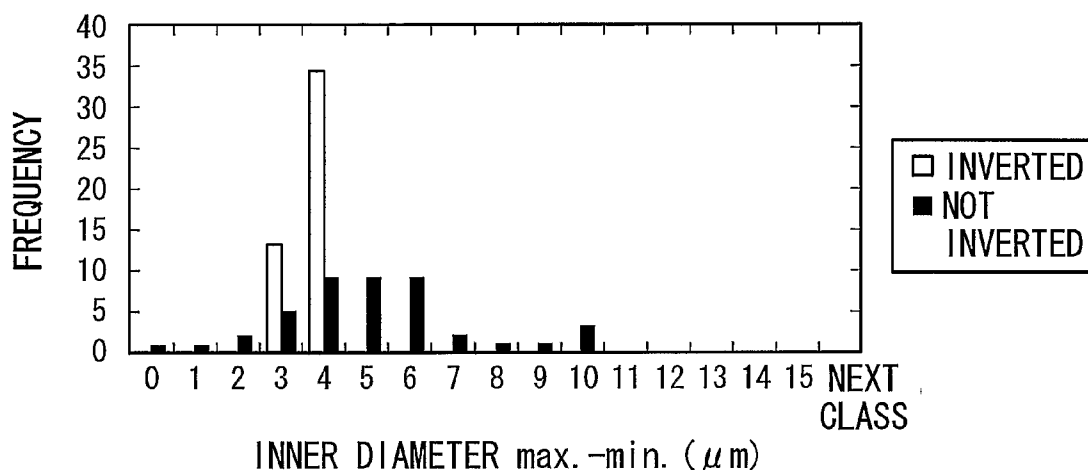
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(54) Title: METHOD OF MANUFACTURING SILICON SUBSTRATES FOR MAGNETIC RECORDING MEDIUM, SILICON SUBSTRATE FOR MAGNETIC RECORDING MEDIUM, MAGNETIC RECORDING MEDIUM, AND MAGNETIC RECORDING APPARATUS



(57) Abstract: A manufacturing method for silicon substrates for a magnetic recording medium has the steps of forming a stack body of a number of silicon substrates which are stacked via spacers therebetween, wherein each silicon substrate has a circular hole at a center of the substrate; immersing the stack body of the silicon substrates in a polishing liquid in which grains are suspended; and polishing inner peripheral end faces of the circular holes of the silicon substrates, wherein in polishing, a polishing brush contacts the end faces while performing a relative rotation between the end faces and the polishing brush, and the stack body of the silicon substrates is inverted during polishing. The step of polishing the inner peripheral end faces may be performed after inner and outer peripheries of the silicon substrate are subjected to chamfering. Preferably, the polishing brush is made of polyamide resin.

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